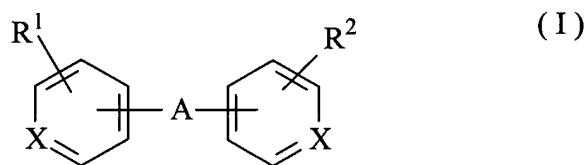


AMENDMENT TO THE ABSTRACT

A negative type resist composition is provided, which provides excellent resolution, satisfactory profile and outstanding process stability: is suitable for exposure using deep ultra violet ray; and comprises alkali soluble resin, acid generator, crosslinking agent, and a basic compound represented by the following formula (I)



wherein, A represents sulfide group, disulfide group or bivalent aliphatic hydrocarbon residue which may be optionally interrupted by imino group, [sulfide group, or disulfide group,] X represents nitrogen atom or $C(NH_2)$, and R^1 and R^2 independently represent hydrogen or alkyl.